

U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					M-11466-8C US		Not yet known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant(s)			
(Use several sheets if necessary)					Chiang, Tony P.; Leeser, Karl F.; Brown, Jeffrey A.; Babcoke, Jason E.			
					Filing Date		Group	
					Herewith		Not yet known	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
EF	AA	5,855,675	01/05/99	Doering et al.	118	719		
	AB	5,879,459	03/09/99	Gadgil et al.	118	715		
	AC	5,916,365	06/29/99	Sherman	117	92		
	AD	6,174,377 B1	01/16/01	Doering et al.	118	729		
EF	AE	6,200,893 B1	03/13/01	Sneh	438	685		
	AF							
	AG							
	AH							
	AI							
	AJ							
	AK							
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
EF	AL	1 052 309 A2	10/05/00	EP				
EF	AM	00/16377	03/23/00	PCT				
	AN							
	AO							
	AP							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
EF	AQ	Peter Singer, Editor-in-chief, "Atomic Layer Deposition Targets Thin Films", Semiconductor International, September 1999, (pp. 40).						
EF	AR	"Ultra-thin films by atomic layer deposition", American Xtal Technology, October 1999 (pp. 37).						
EF	AS	S. M. Rosnagel, IBM Research, A. Sherman and F. Turner, Sherman and Associates, "Plasma-enhanced atomic layer deposition of Ta and Ti for interconnect diffusion barriers, J. Vac. Sci. Technol. B 18(4), Jul/Aug 2000, (pp. 2016-2020).						
Examiner		Date Considered 2/16/06						
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.								